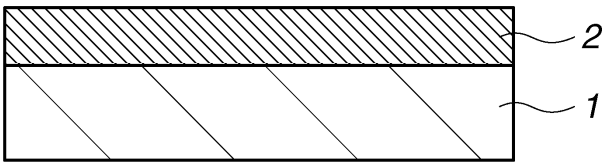
# FIG.1



# FIG.2

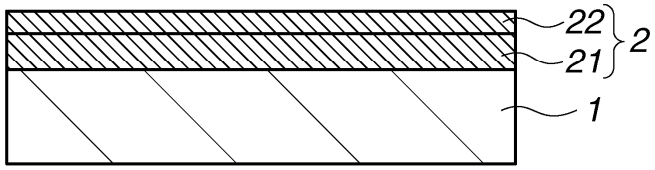


FIG.3A

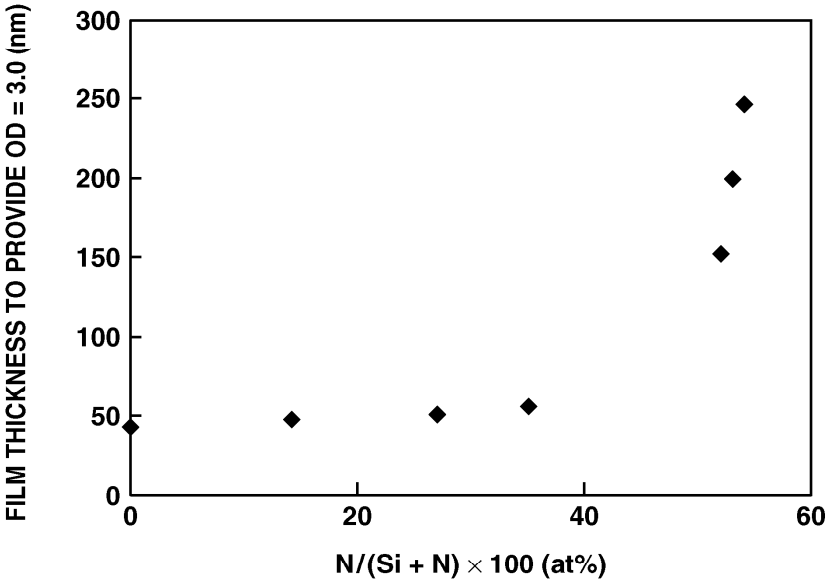
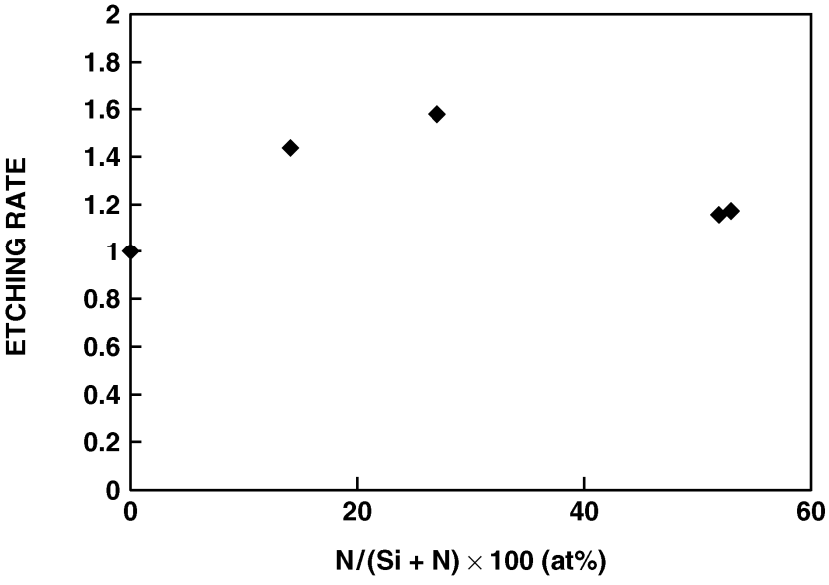

FILM THICKNESS TO PROVIDE OD = 3.0 (nm)
300
250
200
150
100
50
0
0
20
40
60
N/(Si + N) × 100 (at%)

FIG.3B


ETCHING RATE
2
1.8
1.6
1.4
1.2
1
0.8
0.6
0.4
0.2
0
0
20
40
60
N/(Si + N) × 100 (at%)

# FIG.4

